Synthesis and characterization of bis(trialkoxysilymethyl)arenes from related bis(trichlorosilylmethyl)arenes. Comparisons between some organosilicate xerogel materials derived from both

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A series of bis(trialkoxysilylmethyl)aryl compounds 1–17 {[[(RO)₃SiCH₂]₂Ar, R = Me, Et, Pr, Bu, Ar = 1,4-C₆H₄; R = Et, Pr, Bu, Ar = 1,4-C₆H₂Me₂-2,6; R = Et, Pr, Bu, Ar = 1,4-C₆Me₄-2,3,5,6; R = Et, Pr, Bu, Ar = 1,3-C₆H₄; R = Bu, Ar = 1,2-C₆H₄; R = Et, Pr, Bu, Ar = 9,10-C₁₄H₈} prepared from the related bis(trichlorosilylmethyl)aryl compounds and characterised by ¹H, ¹³C and ²⁹Si NMR and IR spectroscopy, and high resolution mass spectrometry. The X-ray crystal structures of two of the bis(trichlorosilylmethyl)aryl precursor compounds are reported. Organosilicate xerogels prepared from the precursors 2, 7 and 12 are discussed.

These have been studied by a combination of solid state NMR spectroscopy, scanning electron microscopy (one case) and nitrogen sorption porosimetry and their properties compared with those of xerogels derived from related bis(trichlorosilylmethyl)arenes.

The idea of tailoring the internal structures of organosilicate xerogels by inserting organic spacers into the siloxane network through the sol-gel processing of compounds with organobridged trifunctional silyl groups, X₃Si-R-SiX₃ was originally reported by Shea.1 A number of studies have focused on the relationship between the nature of the organic group and the microarchitecture of the derived glassy xerogel materials.²⁻⁴ One of our aims was to gauge the extent to which the nature of the functional groups in such organobridged precursors affect properties such as distribution of T^n environments, overall % condensation and surface area in derived gels. We have recently synthesised a series of bis(trichlorosilylmethyl)arenes,⁵ from which we prepared and characterised the corresponding monolithic transparent xerogels. In this paper we report on the related series of bis(trialkoxysilylmethyl)arenes, their conversion to xerogels and some of the properties of these materials, e.g. local chemical structure, by ¹³C and ²⁹Si CP MAS NMR spectroscopy, morphology, by scanning electron microscopy (SEM) and surface area, by nitrogen sorption porosimetry.

Results and Discussion

There are numerous reported methods for the synthesis of organoalkoxysilane compounds, RSi(OR)₃. In addition to direct reactions of organotrichlorosilanes with alcohols⁶ organylation of alkoxychlorosilanes such as (EtO)₃SiCl using lithium7 or sodium8 or Grignard1,7,9 reagents as well as hexachloroplatinic acid promoted organylation^{2,3} are commonly used. We tried without success to use the *p*-xylenediyl dianion 1,4-[CH₂]₂C₆H₄²⁻, as the Grignard reagent in conjunction with Si(OEt)₄ or (Et₃O)₃SiCl to obtain 1,4-[(EtO)₃SiCH₂]₂C₆H₄. Only diethyl ether-insoluble polymer like materials were obtained. Direct reaction of bis(trichlorosilvlmethyl)arenes⁵ with alcohol gave the series of bis(trialkoxysilylmethyl)arenes 1-17. The reactions were performed at room temperature and were quantitative. These compounds broadly follow the properties noted for other organotrialkoxysilanes, and are all readily hydrolysed in moist air and soluble in most organic solvents. Unlike the chloride starting materials these compounds are liquids reflecting weaker intermolecular interactions in the alkoxides and are mostly colourless, apart from 6, 11 and 17. They are deep orange-brown, and are derived

from the similarly coloured solid bis(trichlorosilylmethyl)anthracene.

We previously reported on the molecular structure of

$$X = -CH_{2} - CH_{2} - CH_{2} - 1 R = OMe$$

$$2 R = OEt$$

$$7 R = OPr$$

$$12 R = OBu$$

$$X = -CH_{2} - CH_{2} - 3 R = OEt$$

$$8 R = OPr$$

$$13 R = OBu$$

$$X = -CH_{2} - CH_{2} - 4 R = OEt$$

$$9 R = OPr$$

$$14 R = OBu$$

$$X = -CH_{2} - CH_{2} - 5 R = OEt$$

$$10 R = OPr$$

$$15 R = OBu$$

$$X = -CH_{2} - CH_{2} - 15 R = OBu$$

$$X = -CH_{2} - CH_{2} - 16 R = OBu$$

$$X = -CH_{2} - CH_{2} - CH_{2} - 16 R = OBu$$

$$X = -CH_{2} - CH_{2} - CH_{2} - 16 R = OBu$$

2,5-bis(trichlorosilylmethyl)-*p*-xylene, A,⁵ and have since completed X-ray studies on the related compounds 1,4-bis(trichlorosilylmethyl)benzene, **B**, and 1,3-bis(trichlorosilylmethyl)-benzene, **C** (molecular structures are shown in Fig. 1 and Fig. 2, along with the corresponding structural data). The bond lengths and angles are all within expected ranges and there are no short inter- or intra-molecular contacts. Both the distances Cl_3Si-CH_2 and the angles $Cl_3Si-CH_2-C(Ar)$ are similar in



Fig. 1 Molecular structure of compound B (ellipsoids at the 50% probability level). Selected bond lengths (Å) and angles (°) for compound B: Cl(1)-Si(1) 2.022(1), Cl(2)-Si(1) 2.014(1), Cl(3)-Si(1) 2.022(1), Cl(4)-Si(2) 2.019(1), Cl(5)-Si(2) 2.018(2), Cl(6)-Si(2)2.013(2), Si(1)-C(1) 1.842(4), Si(2)-C(5) 1.816(4), C(1)-Si(1)-Cl(2) 110.9(2), C(1)-Si(1)-Cl(3) 111.0(2), Cl(2)-Si(1)-Cl(3) 107.67(7), C(1)-Si(1)-Cl(1)111.2(1), Cl(2)-Si(1)-Cl(1)108.49(7). Cl(3)-Si(1)-Cl(1) 107.43(6), C(5)-Si(2)-Cl(6) 112.4(2).C(5)-Si(2)-Cl(5)109.7(2), Cl(6)-Si(2)-Cl(5)106.59(8), C(5)-Si(2)-Cl(4)111.4(1), Cl(6)-Si(2)-Cl(4)108.29(7), Cl(5)-Si(2)-Cl(4) 108.28(7), C(2)-C(1)-Si(1) 113.7(3).



Fig. 2 Molecular structure of compound B (ellipsoids at the 50%) probability level). Selected bond lengths (Å) and angles (°) for compound C: Si(1)–C(1) 1.857(10), Si(1)–Cl(2) 1.993(4), Si(1)–Cl(1) 2.009(5), Si(1)–Cl(3) 2.011(4), Si(2)–C(8) 1.836(10), Si(2)–Cl(5) 1.990(4), Si(2)-Cl(6) 2.003(4), Si(2)-Cl(4) 2.013(4), C(1)-Si(1)-Cl(2) 109.8(4), C(1)-Si(1)-Cl(1) 111.4(4), Cl(2)-Si(1)-Cl(1) 109.0(2),C(1)-Si(1)-Cl(3)112.3(4). Cl(2)-Si(1)-Cl(3)107.0(2).110.7(4), Cl(1)-Si(1)-Cl(3) 107.3(2), C(8)-Si(2)-Cl(5) C(8)-Si(2)-Cl(6)112.0(4), Cl(5)-Si(2)-Cl(6)107.4(2), C(8)-Si(2)-Cl(4)Cl(5)-Si(2)-Cl(4)107.7(2), 111.2(4), Cl(6)-Si(2)-Cl(4) 107.5(2), C(2)-C(1)-Si(1) 112.4(7).

A, **B** and **C**. As with **A** the CH₂SiCl₃ groups in **B** and **C** are mutually *trans* about the plane of the arene bridge. Thus there are no obvious structural consequences associated with the additional steric effect of the methyl substituents in **A** compared to **B** and the different substitution pattern in **B** compared to **C**. To the best of our knowledge these are the only compounds with CH₂SiCl₃ functions to be structurally characterised.

Spectroscopic data for compounds 1-17

Analytical and spectroscopic data for compounds 1–17 (¹H, ¹³C and ²⁹Si NMR, IR and m/z) are assembled in Tables 1–11. The spectroscopic data confirm the expected structural features. Correlation data¹⁰ were used for the assignment of arene proton and ¹³C resonances. In the ¹H NMR spectra, Tables 1, 4 and 7, the chemical shifts of the methylene protons in the alkoxysilylmethylanthracene derivatives are *ca.* 1 ppm downfield of the other compounds and the ¹³C chemical shifts for the methylene carbons in the anthrancene derivatives are 6 ppm upfield of those of the other aralkyl bridges. These relative shifts follow the patterns observed for related xylene and 9,10-dimethylanthracene derivatives **6**, **11** and **17**, Table 10, occurred at lower field than in other aralkyl bridged species.

The chemical shifts of the methylene protons in the trialkoxysilvlmethylbenzenes were ca. 1 ppm upfield of those of the corresponding trichloride starting materials as expected on grounds of likely electronegativity differences between alkoxy and chloride groups. The methylene carbons of the aralkyl bridges were shifted ca. 10 ppm upfield from the corresponding trichlorosilyl compounds. In all of the durene derivatives, the signals due to the methylene and the methyl protons of the aralkyl fragment were coincident. Changing the aryl bridge had no effect on the chemical shifts of the alkoxy protons or carbons (Tables 1-9) and these were similar to those of the corresponding alcohols.¹² Similarities between the coupling constants ³J_{CH₃-CH₂} and ³J_{CH₂-CH₂} greatly simplified the multiplicity associated with protons on the alkyl chains of the alkoxy groups in many cases. Thus the total number of lines seen for any given set of equivalent protons followed from the total number, n, of proton neighbours to which they are coupled¹⁰ (see Tables 1, 4, 7). The ²⁹Si NMR chemical shifts, Table 10, were in the range from $\delta - 47.54$ to -53.36, as expected for $-Si(OR)_3$ containing compounds.¹³ The ²⁹Si NMR chemical shift of compound 1 occurred at lower field than those of the others.

In the IR spectra, the characteristic bands,^{10,14} of Si-C, Si-OR and C=C, C-H of the phenyl groups were observed. As with the organotrichlorosilane, the Si-C vibrations occured between 1200 and 1262 cm⁻¹ as expected. The Si-OR vibrations of ethoxy compounds appear as two close bands at *ca*. 1100 cm⁻¹ (ref. 7). The other alkoxy compounds showed one sharp band in this region. Also as with the organotrichlorosilane, no C=C vibrations were observed in durene derivatives. The aromatic ring C-H out of plane deformations generally appeared as a strong band at *ca*. 800 cm⁻¹. In all of the anthracene derivatives, and the ethoxy compounds, the aromatic C-H out of plane vibrations occurred below 800 cm⁻¹, whilst in the others, including 1,3- and 1,2-disubstitued benzenes, this band appeared above 800 cm⁻¹.

The mass spectra fragmentation patterns of compounds 1–17 are assembled in Table 11. $[M]^+$ and $[M-2Si(OR)_3]^+$ fragments appear for compounds 1–17. In addition the $[Si(OR)_3]^+$ fragments were observed for the methoxy compound 1, ethoxy compound 4 and all of the propoxy and butoxy compounds. $[M-Si(OR)_3]^+$ fragments appeared in most of the compounds apart from 1, 10, 15, 16, that is those compounds where the two trialkoxylsilylmethyl groups occupy mutual *ortho* or *meta* positions on the phenyl ring.

Table 1 ¹H NMR assignments in compounds 1–6 (CDCl₃)

		1 2 3 CH ₂ Si(OCH ₂ CH ₃))3			
	1	2	3	4	5	6
OCH ₃ CH ₂	3.49(s, 18H)*		2.23(s, 6H)	2.23(12H)		
aromatic ring	7.03(s, 4H)	7.09(s, 4H)	6.90(s, 2H)		7.14–7.28(m, 4H)	7.43–7.55(m, 4H)
H1 H2 H3	2.18(s, 4H)	2.20(s, 4H) 3.67–3.93(q, 12H) 1.12–1.30(t, 18)	2.10(s, 4H) 3.60–3.86(q, 12H) 1.07–1.24(t, 18H)	2.23(s, 4H) 3.53–3.80(q, 12H) 1.04–1.21(t, 18H)	2.14(s, 4H) 3.64–3.89(q, 12H) 1.08–1.26(t, 18H)	3.21(s, 4H) 3.46–3.73(q, 12H) 0.94–1.11(t, 18H)

Table 213CNMRassignmentsincompounds1-6(CDCl_3,150.90 MHz)

	1 CH-Sill	2 3 OCH.CH.)-			
	1	2	3 3	4	5	6
OCH ₃	50.61					
CH ₃			16.76	16.72		
C1	18.23	19.55	19.35	19.23	20.47	14.46
C2		58.29	58.42	58.26	58.47	58.54
C3		18.20	17.90	17.32	18.04	17.93

Table 3 13 C NMR assignments of ring carbons in compounds 1–6 (CDCl₃, 150.9 MHz)^{*a*}



 ${}^{a}R' = CH_{2}Si(OCH_{3})_{3}; R = CH_{2}Si(OCH_{2}CH_{3})_{3}.$

Sol-gel processing of 1,4-bis(trialkoxysilylmethyl)arenes

We have already reported on the synthesis and properties of a range of organosilicate xerogel materials, XCl, derived through sol-gel processing of 1,4-bis(trichlorosilylmethyl)arene compounds,⁵ and we were interested to compare the properties of similar materials derived from related alkoxy precursors. The conditions used for sol-gel processing of 1,4- $[(RO)_3SiCH_2]_2C_6H_4$ compounds 2 (R = Et), 7 (R = Pr) and 12 (R = Bu) to xerogels X1, X2, X3a and X3b respectively, are summarised in Table 12 with further details given in the Experimental section, and involve HCl acid catalysis. The molar ratio of Si-OR functions to HCl in these sol-gel mixtures are 40-100 and it is possible that some intermediate Si-Cl is formed (Si-OR/H₂O ratios were between 0.5 and 1). Nonetheless times to gelation for the alkoxy compounds were generally longer than previously found for the related chlorosilane compounds. A slower rate of hydrolysis is expected for the alkoxy species.¹⁵ In each case a transparent monolith was formed.

The xerogels X1–X3, Table 12, were studied by both ¹³C and ²⁹Si CPMAS NMR spectroscopy. Chemical shift data are given in Tables 13 and 14. The relative peak areas associated with T^n environments (obtained using GAUSSIAN simulation of the ²⁹Si spectra and where n=0-3 refers to the number of Si–O–Si bonds associated with particular Si sites) in xerogels X1–X3 are given in Table 13. A comparison of the data with

those for the related xerogel **XCI** derived from the chlorosilane, in each case reveals an increase (*ca.* 10%) in the T^2 component at the expense of T^3 . The absence of any T^0 peak for **X1** and **X3b**, both of which were processed in ethanol, is noteworthy. The overall percentage condensation in each case, Table 13, was calculated as previously described,⁴ and is slightly lower than that achieved for the related **XCI** material.

Peak assignments for the ¹³C and CPMAS NMR spectra are given in Table 14. Peaks associated with the organic bridges in the organosilicate framework are close to those previously assigned to the **XCI** xerogel and assignments were confirmed by non-quaternary suppression techniques as previously described.⁴ Other peaks present in these spectra are associated with residual alkoxy groups both as the alcohol and associated with T^n environments. The intensity of these peaks decreased substantially when materials were heated to 200°C at 0.001 Torr for 48 h.

The solvent-free xerogels X1-X3 were found to have BET surface areas $<2 \text{ m}^2 \text{ g}^{-1}$ when examined by nitrogen sorption porosimetry. This contrasts with the XCI material having the same organic bridge but which was microporous with a surface area 600 m² g⁻¹ (ref. 4). It is noteworthy that other bis(trialkoxysilyl)arylenes and alkylenes also gave low surface area materials and this was thought to be a consequence of the non-rigidity of the bridging group in these cases.¹⁶ The different distributions in T^n environments compared to those of XCI coupled with the presence of residual T^n alkoxy groups in X1–X3 represent differences in the local chemical environments which may have effected pore structure although we are not aware of previous correlations of this type. A high resolution SEM (Fig. 3) on a relatively thick film of X3a cast on a glass slide reveals an apparently more densely packed nanoparticulate surface texture than found for the related XCl material.⁴

Further work concerning the use of these materials as confinement matrices for a variety of guest species is in hand. This work illustrates that the formation of xerogels is controlled by a number of factors and that properties can be adjusted by altering the nature of the precursors.

Experimental details

All reactions and manipulations involving moisture sensitive compounds were carried out under purified nitrogen. The bis(trichlorosilylmethyl)arene starting materials were made as previously described.5 The alcohols used were purified by distillation from the corresponding magnesium alkoxides. The bis(trialkoxysilylmethyl)arenes were purified by Schlenk flask to Schlenk flask distillation via a connecting glass tube. A dynamic vacuum was applied through the receiver Schlenk and, with the distillation Schlenk immersed in an oil bath products were collected at 150-180 °C in the liquid nitrogen cooled receiver Schlenk and subsequently stored under nitrogen. Solution phase NMR spectra were recorded on Bruker AW-250 (¹³C, 62.89 MHz; ²⁹Si, 49.66 MHz), Bruker AW-400, Bruker AMX-600 (13C, 150.90 MHz; ²⁹Si, 119.23 MHz) and Bruker WP-80 (¹H, 80 MHz) NMR spectrometers. Spectra were recorded on samples dissolved in dried deuteriated CDCl₃

	$\begin{array}{ccc} 2 & 3 & 4 \\ CH_2Si(OCH_2CH_2CH_3)_3 \end{array}$				
	7	8	9	10	11
CH ₃	_	2.25(s, 6H)	2.24(12H)		
aromatic ring	7.04(s, 4H)	6.90(s, 4H)		6.90–6.98(s, 4H)	7.43–7.58(m, 4H) 8.33–8.46(m, 4H)
H1	2.15(s, 4H)	2.10(s, 4H)	2.24(s, 4H)	2.14(s, 4H)	3.21(s, 4H)
H2	3.55-3.72(t, 12H)	3.60 - 3.65(t, 12H)	3.50-3.66(t, 12H)	3.60 - 3.66(t, 12H)	3.43-3.58(t, 12H)
H3	1.40-1.57(sxt, 12H)	1.46-1.61(sxt, 12H)	1.39–1.64(m, 12H)	1.45-1.60(sxt, 12H)	1.29–1.54(m, 12H)
H4	0.78–0.96(t, 18H)	0.86-0.93(t, 18H)	0.86–1.11(t, 18H)	0.84–0.90(t, 18H)	0.66–0.82(t, 18H)

 Table 5
 ¹³C
 NMR assignments
 in compounds
 7–11
 (CDCl₃, 150.90 MHz)

	2 3 4 CH ₂ Si(OCH ₂ CH ₂ CH ₂) ₂					
	7	8	9	10	11	
CH ₃		16.87	16.77			
C1	19.42	19.43	19.28	19.97	14.18	
C2	64.48	64.45	64.32	64.49	64.42	
C3	25.51	25.51	25.48	25.49	25.33	
C4	10.08	10.05	11.17	10.06	9.94	

and kept under nitrogen atmosphere. All chemical shifts (δ in ppm) were referenced to appropriate nuclei in tetramethylsilane. IR spectra were recorded on a Perkin-Elmer FTIR 1720X spectrophotometer, using neat liquids between two KBr plates. Mass spectra were obtained on a Kratos MS 50RF mass spectrometer. The samples were sealed in nitrogen-filled Pyrex capillary tubes. The capillaries were opened and mounted in the probe under a nitrogen atmosphere. A summary of the observed fragmentation patterns is given in Table 11. Elemental analysis (C,H) was obtained from University College London Analytical Service. The samples were sealed under nitrogen in a glass tube.

Crystallographic measurements were made using a CAD-4 diffractometer in ω -2 θ scan mode, on selected single crystals mounted inside 0.7 mm glass capillaries, which were flame sealed under nitrogen. The structures were solved by direct methods and refined by least-squares analysis.

The solid state ¹³C and ²⁹Si NMR spectra were acquired using cross polarization (CP) magic angle spinning (MAS), and high-power proton decoupling on a Bruker MSL-300 spectrometer. Typical conditions were 2 ms contact time, 1 s recycle delay, a 90° pulse length of 4.07 μ s and a spinning speed of 4.5 kHz. The ¹³C and ²⁹Si frequencies were 75.5 and 59.6 MHz, respectively. All spectra were recorded at room temperature and chemical shifts are quoted relative to SiMe₄. Scanning electron micrographs were obtained using a JEOL JC6300 Scanning Electron Microscope.

Surface area measurements were obtained using a Micromeretrics ASAP 2400 instrument.

Preparation of 1,4-bis(trimethoxysilylmethyl)benzene 1. 1,4-Bis(trichlorosilylmethyl)benzene (2.30 g, 6.2 mmol) was dissolved in methanol (40 cm³) and stirred overnight. Removal of the excess methanol afforded the product as a colourless liquid (1.82 g, yield 85%). $\delta_{\rm H}$ (80 MHz, CDCl₃): 2.18(s, 4H), 3.49(s, 18H), 7.03(s, 4H). $\delta_{\rm si}$ (119.23 MHz, CDCl₃): -47.54. $\delta_{\rm C}$ (150.9 MHz, CDCl₃): 18.23, 50.61, 128.58, 132.93. $\nu/{\rm cm}^{-1}$ (KBr): 2944(s), 2842(s), 1904(w), 1512(s), 1462(m), 1422(m), 1401(m), 1192(s), 1088(s, b), 1023(m), 849(s), 804(s), 747(m), 730(m), 664(w), 641(w), 563(w), 522(m), 478(m). m/z (% relative intensity) theoretical m/z: C₁₄H₂₆Si₂O₆, 346.1280(66.2)-346.1268. C₃H₉O₃Si, 121.0321(100)121.0321. C₈H₈, 104.0639-(45.0)104.0626.

 Table 6
 ¹³C NMR assignments of ring carbons in compounds 7–11

 (CDCl₃, 150.90 MHz)^a



 ${}^{a}R = CH_{2}Si(OCH_{2}CH_{2}CH_{3})_{3}.$

Preparation of 1,4-bis(triethoxysilylmethyl)benzene 2. Prepared as described for **1** from 1,4-bis(trichlorosilylmethyl)benzene (2.00 g, 5.36 mmol) and ethanol (40 cm³); after further distillation, yield, 1.84 g (80%). v/cm^{-1} (KBr): 2975(s), 2927(s), 2890(s), 1512(m), 1483(w), 1443(w), 1422(w), 1391(m), 1366(w), 1295(w), 1262(w), 1222(m), 1170(s), 1104(s), 1083(s), 960(s), 839(m), 799(s), 723(w), 565(w), 528(w), 483(w). m/z (% relative intensity) theoretical m/z: C₂₀H₃₈Si₂O₆,

Table 7 ¹H NMR assignments in compounds 12–17 (CDCl₃)

	1 2 3 4 $5CH2Si(OCH2CH2CH2CH2CH2),$					
	12	13 13	14	15	16	17
CH ₃		2.21(s, 6H)	2.35(s, 12H)			
aromatic	7.03(s, 4H)	6.90(s, 2H)		6.90-6.98(m, 4H)	7.05-7.12(m, 4H)	7.45-7.57(m, 4H)
ring						8.33-8.45(m, 4H)
H1	2.14(s, 4H)	2.09(s, 4H)	2.35(s, 4H)	2.13(s, 4H)	2.27(s, 4H)	3.21(s, 4H)
H2	3.65-3.70(t, 12H)	3.61-3.75(t, 12H)		3.65-3.70(t, 12H)	3.58-3.68(t, 12H)	3.48-3.63(t, 12H)
H3	1.44–1.55(p, 12H)	1.15-1.59(m, 24H)	1.27-1.71(m, 24H)	1.42-1.55(p, 12H)	1.26-1.69(m, 24H)	1.11 - 1.57 (m, 24H)
H4	1.27–1.41(sxt, 12H)			1.26–1.41(sxt, 12H)		
H5	0.87–0.93(t, 18H)	0.82–1.00(t, 18H)	0.81-1.00(t, 18H)	0.87–0.92(t, 18H)	0.80–0.98(t, 18H)	0.70–0.96(t, 18H)

Table 813CNMRassignmentsincompounds12–17(CDCl3,150.90 MHz)

		1 CH ₂ S	2 3 i(OCH ₂ CH	4 5 1 ₂ CH ₂ CH	3)3	
	12	13	14	15	16	17
CH ₃		16.74	16.06			
C1	19.59	19.51	19.44	20.02	20.31	14.30
C2	62.74	62.52	62.42	62.60	62.55	62.59
C3	34.61	34.47	34.47	34.47	34.47	34.20
C4	18.93	18.80	18.81	18.79	18.79	18.69
C5	13.89	13.89	13.83	13.66	13.64	13.62

430.2196(76.2) 430.2207. $C_{14}H_{23}O_3Si,\ 267.1359(5.4)267.1417.$
 $C_8H_8, 104.0661(100)104.0626.$ Calc. for $C_{20}H_{38}Si_2O_6$: C
, 55.76; H, 8.89. Found: C, 54.68; H: 8.77%

Preparation of 2,5-bis(triethoxysilylmethyl)-*p*-xylene **3.** Prepared as described for **1** from **2**, 5-bis(trichlorosilylmethyl)*p*-xylene (2.60 g, 6.48 mmol) and ethanol (40 cm³). Yield, 2.73 g (92%). v/cm^{-1} (KBr): 2973(s), 2927(s), 2884(s), 1559(m), 1541(m), 1506(m), 1457(m), 1390(s), 1201(s), 1169(s), 1083(s), 960(s), 885(w), 838(m), 797(s), 761(s), 669(w), 507(w), 471(m). m/z (% relative intensity) theoretical m/z. C₂₂H₄₂Si₂O₆, 458.2535(36.1)458.2520. C₁₆H₂₇O₃Si, 295.1662(8.3)295.1729. C₁₀H₁₂,132.0949(100)132.0939.

Preparation of 1,4-bis(triethoxysilyImethyl)durene 4. Prepared as described for 1 from 1,4-bis(trichlorosilyImethyl)durene (2.4 g, 5.59 mmol) and ethanol (40 cm³). Yield, 2.12 g (78%). v/cm^{-1} (KBr): 2974(s), 2926(s), 2887(s), 1481(w), 1442(m), 1391(s), 1366(w), 1295(w), 1250(w), 1169(s), 1083(s), 960(s), 855(m), 789(s), 755(w), 554(w). m/z (% relative intensity) theoretical m/z. C₂₄H₄₆Si₂O₆,486.2829(39.6)486.2833. C₁₈H₃₁O₃Si, 323.2012(4.0%)320.2042. C₁₂H₁₆, 160.1264(9.8)-160.1252.

Preparationof1,3-bis(triethoxysilylmethyl)benzene5.Prepared as described for 1 from 1,3-bis(trichlorosilylmethyl)
benzene (2.6 g, 6.97 mmol) and ethanol (40 cm³). Yield, 2.52 g
(84%). m/z (% relative intensity) theoretical m/z. C₂₀H₃₈Si₂O₆,
430.2189(2.5)430.2207.C₁₄H₂₃O₃Si,267.1437(1.0)267.1417.
C₈H₈, 104.0600(13.4)104.0626.

Preparation of 9,10-bis(triethoxysilylmethyl)anthracene 6. Prepared as described for 1 from 9,10-bis(trichlorosilylmethyl)anthracene (2.0 g, 4.23 mmol) and ethanol (40 cm³). Yield, 1.91 g (85%). v/cm⁻¹ (KBr): 2974(s), 2926(s), 2888(s), 1457(w), 1447(s), 1389(s), 1367(s), 1294(w), 1261(w), 1168(s), 1083(s), 1026(s), 962(s), 870(w), 794(s), 753(s), 664(w), 459(w). *m/z* (% relative intensity) theoretical *m/z*. C₂₈H₄₂Si₂O₆, 530.2514-(100%)530.2520. C₂₂H₂₇O₃Si, 367.1655(2.0)367.1729. C₁₆H₁₂, 204.0961(8.6)204.0939.

Preparation of 1,4-bis(tripropoxysilylmethyl)benzene 7. Prepared as described for **1** from 1,4-bis(trichlorosilylmethyl)-

Table 9 ¹³C NMR assignments of ring carbons in compounds 12–17 (CDCl₃, 150.90 MHz)



 ${}^{a}\mathbf{R} = \mathbf{CH}_{2}\mathbf{Si}(\mathbf{OCH}_{2}\mathbf{CH}_{2}\mathbf{CH}_{2}\mathbf{CH}_{3})_{3}.$

Table 10²⁹Si chemical shifts of compounds 1–17 in CDCl₃

compound	chemical shift δ
1	- 17.5l
2	-50.78
3	-51.67
4	-51.69
5	-50.90
6	- 53.36
7	-51.06
8	-51.00
9	-51.83
10	-51.18
11	-53.20
12	-50.68
13	- 50.61
14	-50.80
15	-51.05
16	-50.78
17	-52.16

benzene (1.8 g, 4.83 mmol) and propanol (40 cm³). Yield, 2.36 g (95%). v/cm^{-1} (KBr): 2962(s), 2936(s), 2877(s), 1512(m), 1463(m), 1422(w), 1391(m), 1261(m), 1221(m), 1171(m), 1154(m), 1088(s,b), 1017(s), 916(w), 899(w), 878(w), 850(s), 757(m), 567(w), 528(w), 419(m). m/z (% relative intensity) theoretical m/z. $C_{26}H_{50}Si_2O_6$, 514.3146(45.3)514.3146. $C_{17}H_{29}O_3Si$, 309.1829(4.7)309.1886. $C_9H_{21}O_3Si$, 205.1266-(99.4)205.1260. C_8H_8 , 104.0639(100)104.0626.

Table 13 ²⁹Si CPMAS chemical shift data (δ), relative areas of T^n environments and overall % condensation

xerogel	δ, T^0	δ, T^1	δ, T^2	δ, T^3	% conden- sation
XCl	-18.0, 5.2	-53.5, 5.3	-62.0, 51.3	-71.0, 38.2	74.2
X1 X2	175 50	-53.0,8.3	-61.9,73.2	-70.7, 18.6	70.4 68 5
X3a	-17.5, 5.9 -18.4, 4.3	-53.9, 9.3 -53.4, 4.7	-61.7, 61.4	-70.2, 20.0 -70.1, 29.6	72.3
X3b	,	-53.8, 8.8	-62.2, 66.6	-70.8, 24.6	72.1

Table 14 13 C CP MAS chemical shift data and chemical shift assignments

xerogel	arene carbons	$-CH_2 (T^1 - T^3)$	$-CH_2$ (T^0)	residual- SiOR/ROH
XCI	129.6, 134.1	22.5	0.8	
X1	129.5, 133.9	22.0		58.7, 18.1
X2	129.5, 133.8	22.4	0.5	64.8, 26.1, 10.8
X3a	129.6, 133.8	22.5	1.4	62.7, 35.0, 19.7, 14.3
X3b	129.5, 134.0	21.9		62.4, 34.9, 19.6, 14.5

Preparationof1,4-bis(tripropoxysilylmethyl)durene9.Prepared as described for 1 from 1,4-bis(trichloroxylsilylmethyl)durene (2.4 g, 5.59 mmol) and propanol (40 cm³). Yield,2.96 g(93%). $\delta_{\rm H}$ (80 MHz, CDCl₃): 0.86-1.11(t, 18H),1.39-1.64(m, 12H), 2.24(s, 16H), 3.50-3.66(q, 12H). v/cm^{-1} (KBr): 2962(s), 2935(s), 2876(s), 1458(m), 1437(w), 1420(w),1391(m), 1261(m), 1173(w), 1153(w), 1087(s,b), 1017(s), 899(w),863(m), 830(m), 754(m), 555(w).m/z(% relative intensity)theoreticalm/z. $C_{21}H_{37}O_3$ Si, 365.2438(5.0)365.2512. $C_9H_{21}O_3$ Si, 205.0530-(22.6)205.1260. $C_{12}H_{16}$, 160.1226(3.3)160.1252.

Preparation of 1,3-bis(tripropoxysilylmethyl)benzene 10. Prepared as described for 1 from 1,3-bis(trichlorosilylmethyl)benzene (2.60 g, 6.97 mmol) and propanol (40 cm^3). Yield, 3.40 g (95%). v/cm⁻¹ (KBr): 2962(s), 2936(s), 2877(s), 1604(w),

compound	typical fragments
1	$[M]^+, [M-2Si(OR)_3]^+, [Si(OR)_3]^+$
2	$[M]^+$, $[M-2Si(OR)_3]^+$, $[M-Si(OR)_3]^+$
3	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+$
4	$[M]^+$, $[M-2Si(OR)_3]^+$, $[M-Si(OR)_3]^+$, $[Si(OR)_3]^+$
5	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+$
6	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+$
7	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+, [Si(OR)_3]^+$
8	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+, [Si(OR)_3]^+$
9	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+, [Si(OR)_3]^+$
10	$[M]^+, [M-2Si(OR)_3]^+, [Si(OR)_3]^+$
11	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+, [Si(OR)_3]^+$
12	$[M]^+$, $[M-2Si(OR)_3]^+$, $[M-Si(OR)_3]^+$, $[Si(OR)_3]^+$
13	$[M]^+$, $[M-2Si(OR)_3]^+$, $[M-Si(OR)_3]^+$, $[Si(OR)_3]^+$
14	$[M]^+$, $[M-2Si(OR)_3]^+$, $[M-Si(OR)_3]^+$, $[Si(OR)_3]^+$
15	$[M]^+, [M-2Si(OR)_3]^+, [Si(OR)_3]^+$
16	$[M]^+, [M-2Si(OR)_3]^+, [Si(OR)_3]^+$
17	$[M]^+, [M-2Si(OR)_3]^+, [M-Si(OR)_3]^+, [M-Si(OR)_3]^+, [Si(OR)_3]^+$

Table 11 Typical fragments in mass spectrum of compounds 1-17

 Table 12 Conditions for formation of xerogels

xerogel	precursor(mass/g)	solvent (volume/cm ³)	catalyst	time to gelation/d
XCI	$1.4-\{Cl_3SiCH_2\}_2C_6H_4$ (1.0)	THF(10)	0.11 cm ³ of 0.1 м HCl	1
X1	$1,4-\{(EtO)_3SiCH_2\}_2C_6H_4$ (2.0)	EtOH(10)	0.4 cm ³ of 0.1 м HCl	6
X2	$1,4-\{(PrO)_{3}SiCH_{2}\}_{2}C_{6}H_{4}(1.89)$	PrOH(10)	0.35 cm ³ of 0.1 м HCl	60
X3a	$1,4-\{(BuO)_3SiCH_2\}_2C_6H_4(2.35)$	BuOH(10)	1.0 cm ³ of 0.1 м HCl	21
X3b	$1,4-\{(BuO)_{3}SiCH_{2}\}_{2}C_{6}H_{4}(2.1)$	EtOH(5)	0.35 cm ³ of 0.1 м HCl	4



Fig. 3 Scanning electron micrograph showing nanoparticulate surface of film of X3a

1559(w), 1507(w), 1474(w), 1458(m), 1438(w), 1392(m), 1260(m), 1170(m), 1154(m), 1087(s,b), 1017(s), 930(w), 899(w), 847(s), 800(m), 755(w), 703(w), 472(w). m/z (% relative intensity) theoretical m/z. C₂₆H₅₀Si₂O₆, 514.3142(20.1)514.3146. C₉H₂₁O₃Si, 205.1252(100),205.1260. C₈H₈, 104.0613(6.6)-104.0626.

Preparation of 9,10-bis(tripropoxysilylmethyl)anthracene 11. Prepared as described for (1) from 9,10-bis(trichlorosilyl methyl)anthracene (2.00 g, 4.23 mmol) and propanol (40 cm³). Yield, 2.39 g (92%). ν/cm^{-1} (KBr): 2961(s), 2934(s), 2876(s), 1473(w), 1457(m), 1387(w), 1369(m), 1261(m), 1169(m), 1087(s,b), 1018(s), 881(m), 840(m), 808(m), 746(s), 670(w), 420(w). m/z (% relative intensity) theoretical m/z. C₃₄H₅₄Si₂O₆, 614.3434(41.9)614.3459. C₂₅H₃₃O₃Si, 409.2172(1.7)409.2199. C₉H₂₁O₃Si, 205.1145(100)205.1260. C₁₆H₁₂, 204.0897(16.1)-204.0939.

Preparation of 1,4-bis(tributoxysilylmethyl)benzene 12. Prepared as described for **1** from 1,4-bis(trichlorosilylmethyl)benzene (4.00 g, 10.72 mmol) and butanol (50 cm³). After further distillation 5.45 g (85%) colourless liquid was obtained. $\delta_{\rm C}$ (62.90 MHz, CDCl₃): 13.89, 18.93, 19.59, 34.61, 62.74, 128.79, 133.44. *v*/cm⁻¹ (KBr): 2959(s), 2934(s), 2874(s), 1512(m), 1465(m), 1385(m), 1301(w), 1262(w), 1222(w), 1171(w), 1093(s), 1041(s), 988(m), 899(m), 841(m), 801(m), 746(w), 567(w), 532(w). *m/z* (% relative intensity) theoretical *m/z*. C₃₂H₆₂Si₂O₆, 598.4085(100)598.4085. C₂₀H₃₅O₃Si, 351.2366(1.3)351.2356. C₁₂H₂₇O₃Si, 247.1708(48.5)247.1729. C₈H₈, 104.0633 (19.7)104.0626. Calc. for C₃₂H₆₂Si₂O₆: C, 64.16; H, 10.43. Found: C, 63.13; H: 10.70.

Preparation of 2,5-bis (tributoxysilylmethyl)-*p*-xylene 13. Prepared as described for 1 from 2,5-bis (trichlorosilylmethyl)*p*-xylene (2.60 g, 6.48 mmol) and butanol (40 cm³). Yield, 3.49 g (86%). v/cm^{-1} (KBr): 2959(s), 2933(s), 2874(s), 1559(w), 1541(w), 1506(s), 1459(s), 1386(s), 1261(s), 1234(w), 1201(w), 1168(s), 1093(s,b), 1041(s), 988(s), 898(s), 837(w), 801(s), 734(w), 462(w), 442(w). m/z (% relative intensity) theoretical m/z: C₃₄H₆₆Si₂O₆, 626.4395(41.0)626.4397. C₂₂H₃₉O₃Si, 379.2733-(6.4)379.2668. C₁₂H₂₇O₃Si, 247.1721(34.2)247.1729. C₁₀H₁₂, 132.0937(82.4)132.0939.

Preparation of 1,4-bis(tributoxysilylmethyl)durene 14. Prepared as described for **1** from 1,4-bis(trichlorosilylmethyl)durene (2.4 g, 5.59 mmol) and propanol (40 cm³). Yield, 3.44 g (94%). ν/cm^{-1} (KBr): 2959(s), 2933(s), 2874(s), 1464(s), 1433(w), 1384(s), 1298(w), 1262(m), 1235(w), 1172(w), 1093(s,b), 1041(s), 1010(w), 987(s), 900(s), 831(w), 798(m), 773(w), 735(s), 428(w). m/z (% relative intensity) theoretical m/z: C₃₆H₇₀Si₂O6, **Preparation of 1,3-bis(tributoxysilylmethyl)benzene 15.** Prepared as described for 1 from 1,3-bis(trichlorosilylmethyl)benzene (2.60 g, 6.97 mmol) and butanol (40 cm³). Yield, 3.96 g (95%). v/cm^{-1} (KBr): 2959(s), 2933(s), 2874(s), 1604(m), 1585(w), 1465(s), 1386(s), 1300(w), 1261(w), 1235(w), 1170(w), 1152(w), 1093(s) 1041(s), 1010(w), 988(s), 930(m), 899(s), 835(w), 806(s), 736(m), 702(w), 455(w). m/z (% relative intensity) theoretical m/z C₃₂H₆₂Si₂O₆, 598.4080(14.0)598.4085. C₁₂H₂₇O₃Si, 247.1653(100)247.1729. C₈H₈, 104.0636(56.1)-104.0626. Calc. for C₃₂H₆₂Si₂O₆: C, 64.16; H, 10.43. Found: C, 63.04; H: 10.38%.

Preparation of 9,10-bis(tributoxysilylmethyl)anthracene 17. Prepared as described for 1 from 9, 10-bis(trichlorosilylmethyl)anthracene (2.00 g, 4.23 mmol) and butanol (40cm³). Yield, 2.80 g (95%). m/z (% relative intensity) theoretical m/z C₄₀H₆₆Si₂O₆, 698.4403(100)698.4398. C₂₈H₃₉O₃Si, 451.2728(10.8)451.2669. C₁₂H₂₇O₃Si, 247.1726(57.8)247.1729. C₁₆H₁₂, 204.0936(37.9)204.0939.

General procedure for the preparation of xerogels X1, X2, X3a, X3b. In general a clear solution of the alkoxy compound, 1,4-bis(RO₃SiCH₂)₂C₆H₄ (R = Et, Pr, Bu) in the appropriate solvent (see Table 12) was prepared under nitrogen in a Pyrex round-bottomed flask and subsequently treated with aqueous HCl (0.11 cm³). This mixture was vigorously stirred to a clear sol, and left to gel in a static nitrogen atmosphere. No precipitation was observed and clear transparent gels subsequently formed. Gelation occured within 1–60 d. The wet gels were left to age for a further 24 h after which drying commenced through two small (diameter *ca*. 1 mm) pin-holes for several days. Subsequently, the whole sample was exposed to air for further slow drying for three weeks. The dried xerogels were obtained as transparent orange coloured mono-liths. Precise experimental quantities used are given in Table 12.

X-Ray crystallography

Crystal data for compound **B**, C₈H₈Cl₆Si₂, M = 373.02, monoclinic space group $P2_1/c$; with a = 8.9956(10), b = 13.035(2), c = 13.460(2) Å, $\beta = 103.85(1)^\circ$, V = 532.3(4) Å³, Z = 4, D_c 1.617 g cm⁻³, F = 1.249 mm⁻¹, (000) = 744, 3087 reflections were measured using Mo-K α ($\lambda = 0.71069$ Å) radiation. 2684 independent reflections were measured, θ range 2.21 $<\theta < 24.97^\circ$. The structure was solved by direct methods and difference Fourier technique (SHELXS-86).¹⁷ Refinement was carried out with full-matrix least-squares analysis on F^2 (SHELXL-93)¹⁸. $R = \sum |F_o - F_c| / \sum F_o = 0.0406$ [1710 reflections with $I > 2\sigma(I)$]. $wR2 = \{\sum [w(F_o^2 - F_c^2)^2] \}^{1/2} = 0.0928; w = 1/[\sigma^2(F_o^2) + (0.0458P)^2 + 0.0.34P]$ where $P = (F_o^2 + 2F_c^2)/3$, and residual electron density 0.411/-0.327 e Å³.

Crystal data for compound C, C₈ H₈ Cl₆ Si₂, M=373.02, triclinic, space group $P\bar{1}$; with a=9.895(1), b=10.305(1), c=15.778(2) Å, $\alpha=89.6(1)$, $\beta=101.98(2)$, $\gamma=91.29(1)^{\circ}$, V=1573.4(3) Å³, Z=4, $D_c=1.617$ g cm⁻³, $\mu=1.216$ mm⁻¹, F(000)=744, 4774 reflections were measured using Mo-K α ($\lambda=0.71069$ Å) radiation. 4378 independent reflections were measured, θ range $1.98^{\circ} < \theta < 22.99^{\circ}$). The structure was solved by direct methods and difference Fourier technique (SHELXS-86).¹³ Refinement was carried out with full-matrix least-squares analysis on F^2 (SHELXL-93).¹⁴ $R=\sum/F_o-F_c$ $F_o=0.0824$ [2198 reflections with $I>2\sigma(I)$]. wR2= $\{\sum[w(F_o^2-F_c)^2]\sum[w(F_o^2)^2]/\}^{1/2}=0.0928$; $w=1/[\sigma^2(F_o^2)+$ (0.1546P)² + 0.00P] where $P=(F_o^2+2F_c^2)/3$, and residual electron density 0.489/-0.369 e Å³.

Atomic coordinates, thermal parameters, and bond lengths and angles have been deposited at the Cambridge Crystallographic Data Centre (CCDC). See Information for Authors, J. Mater, Chem., 1997, Issue 1. Any request to the CCDC for this material should quote the full literature citation and the reference number 1145/33.

D.L.O. and A.C.S. thank Unilever for support, and the Airey Neave Trust for financial assistance (to D.L.O.). We thank Peter Cook and Greg Coumbarides (QMW) for mass spectra and NMR spectra; we thank Peter Haycock, Harold Toms and Patrick J. Barrie of the University of London Intercollegiate NMR Research Facilities at Queen Mary and Westfield College and University College London, for NMR spectra.

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Paper 6/07633E; Received 11th November, 1996